## **Supporting Information**

## Three-dimensional network of coaxial carbon nanotube/manganese oxides electrode for supercapacitors

S. J. Cho,<sup>a‡</sup> R. Chen,<sup>a‡</sup> M. Lee,<sup>b</sup> Y. S. Kang,<sup>c</sup> S. Lee,<sup>d</sup> and H. Lee<sup>a,e</sup>

<sup>a.</sup> Department of Chemistry, Hanyang University, Seoul 04763, Korea.

<sup>b.</sup> Center for Nanobio Integration & Convergence Engineering, National Nanofab Center, Daejeon 34141, Korea.

<sup>c</sup> Department of Energy Engineering, Hanyang University, Seoul 04763, Korea.

<sup>d.</sup> Department of Advanced Materials Engineering, University of Suwon, Gyeonggi-do 18323, Korea.

<sup>e</sup> Institute of Nano Science and Technology, Hanyang University, Seoul 04763, Korea.

<sup>+</sup> S. J. Cho and R. Chen contributed equally to this work.

## **Experimental Section**

*Preparing of 3DNC/MnO<sub>x</sub> Composites:* 

As described previously, <sup>25, 27</sup> the fabrication procedure of MnO<sub>x</sub> coated 3DNC nanostructure is briefly shown as follows. Si pillar structures were fabricated on Si (100) wafers (N-type, Siltron) via deep reactive ion etching process. The bared Si wafer (without etching process) was used for comparison. Those two kinds of Si substrates were socked in a piranha solution ( $H_2SO_4$ : $H_2O_2=7$ :3) for 3 hours in order to clean and modify the Si surface with hydroxyl groups. After rinsing with de-ionized (DI) water several times, the Si pillar substrates were dipped into the Fe–Mo catalyst solution, which was made of Fe(NO<sub>3</sub>)<sub>3</sub>·9H<sub>2</sub>O (Junsei) and Mo solution (ICP/DCP standard solution, Aldrich), for 60 min, and then fully rinsed with ethanol several times. The CNTs were synthesized on Si substrates in C<sub>2</sub>H<sub>2</sub> ambient (750°C, 10 sccm, 20 min) after NH<sub>3</sub> treatment (750°C, 300 sccm, 10 min) by means of low pressure thermal CVD.

A thin layer of Pt was firstly coated on synthesized CNTs using ion sputter (E-1045, Hitachi). Pt deposition was processed for 200 sec with an applied current of 15 mA. The deposition of  $MnO_x$  was processed by potentiostat/galvanostat work station (WPG 100, WonATech) in a three-electrode system. Pt coated 3DNC (1×0.5cm) was used as working electrode. Pt wire (>99%, Aldrich) and standard calomel electrode (SCE, BASi, USA) were used as counter electrode and reference electrode, respectively. 0.02 M of potassium permanganate (≤99.3%, Samchun Chemical) was used as precursor. The applied current for deposition was 1mA for 1 sec with 60 sec intervals of zero current. The total coating time was 3 min. After deposition, all of the samples were dipped into DI-water several times to wash off residual precursor and annealed at 200 °C for 2 hours. The loading mass of manganese was about 0.108 mg cm<sup>-2</sup>.

## Materials Characterization and Electrochemical Evaluation:

Sample morphologies were characterized by field-emission scanning electron microscope (FE-SEM, S-4800, Hitachi), transmission electron spectroscope (TEM, JEOL-2100F, JEOL), and X-ray photoelectron spectroscopy (XPS, Al Kα excitation

laser, ESCA 2000). The electrochemical properties of samples were determined by cyclic voltammetry (CV) in the potential range of 0 to 0.8V at a scan rate of 10, 20, 50 and 100 mV s<sup>-1</sup> by the same three-electrode configuration in 1M Na<sub>2</sub>SO<sub>4</sub> aqueous solution (>99.9%, Aldrich). Life cycle tests were characterized by CV curves at a rate of 100 mV s<sup>-1</sup> for 2000 cycles. The ohmic cell information was characterized by electrochemical impedance spectroscopy (AUT 302N, Autolab). The electrolyte and electrodes were the same as with the CV curve test. Solution resistance and charge transfer resistance were characterized over a frequency range from 100 kHz to 10 Hz at sinusoidal voltage amplitude of 5 mV and room temperature.



**Fig. S1** SEM images of (a) amorphous CNTs grown on flat Si template; (b) manganese oxide deposited 2DNC; (c) CV curves of 2DNC/MnO<sub>x</sub> at scan rate of 10, 20, 50 and 100 mV s<sup>-1</sup> in 1M Na<sub>2</sub>SO<sub>4</sub> solution and the specific capacitance are 271, 201, 117 and 60 F g<sup>-1</sup>, respectively.



**Fig. S2** Specific capacitance of 3DNC/MnO<sub>x</sub> for different loading time. The calculated  $C_{sp}$  values of 3DNC/MnO<sub>x</sub> at 10 mV s<sup>-1</sup> are 294, 220, 193, 168 and 167 F g<sup>-1</sup> at loading time of 3, 6, 9, 12 and 15 min, respectively.



**Fig. S3** Nyquist plots of 3DNC/MnO<sub>x</sub> for different loading time. According to the Randle circuit, the calculated average  $R_s$  is about 11.66  $\Omega$ . The calculated  $R_{CT}$  for 0, 3, 6, 9, 12 and 15 min of deposition time are 23.6, 54.88, 93.31, 139.36, 190.94 and 242.96  $\Omega$ , respectively. The calculated  $Z_w$  values are 11.70, 11.86, 16.57, 39.93, and 139.5  $\Omega$ , respectively. The  $Z_w$  values are 45° slope portions of curves, and these values are results of the frequency dependence of ion diffusion and transport. Thicker layer of MnO<sub>x</sub> hinders the charge transfer reaction because part of the MnO<sub>x</sub> layer can not react with electrolytes. As the deposition time increased, the specific capacitance per unit mass decreases due to decreased ion diffusion.

Sample -	Peak intensitiy		Dook Llookt Dotio	C (F c <sup>-1</sup> )
	Mn 2p 3/2 (CPS)	O 1s (CPS)	reak neght Katio	⊂ <sub>sp</sub> (r g ⁻)
Mn <sub>2</sub> O <sub>3</sub>	-	-	1.15	
1	36947.4	35753.9	1.03	190
2	36240.4	35664.2	1.01	250
3	37576.5	37612.8	0.99	294
MnO <sub>2</sub>	_	-	0.95	

**Table S1.** Peak intensities and peak height ratio of Mn 2p 3/2 and O 1s for  $3DNC/MnO_x$ . Specific capacitance is also measured by CV. The peak height ratio data of  $Mn_2O_3$  and  $MnO_2$  were taken from reference.<sup>31</sup>



Fig. S4 Graph of peak height ratio (left) and specific capacitance (right) for 3DNC/MnO<sub>x</sub> with different intervals.



Fig. S5 SEM images of  $3DNC/MnO_x$  coaxial bundles before (a) and after (b) 2000 cycling test.